

Roll-2-Roll imprinting solutions in lighting

*Recent progress in UV-Nanoimprinting of
Micro Optics on Foil*

Paul Hartmann

**JOANNEUM RESEARCH
MATERIALS**

Institute for Sensors, Photonics and Manufacturing Technologies

Amsterdam, December 2nd, 2024

www.joanneum.at/materials

MATERIALS

Institute for Sensors, Photonics and Manufacturing Technologies

2

■ Director:

■ Paul Hartmann

■ 5 Research Groups

~ 100 Employees

■ 2 Locations in Styria

■ Weiz

■ Niklasdorf

■ 1 Location in Burgenland

■ Pinkafeld



**Hybrid Electronics
and Patterning**
Barbara Stadlober

**Light and Optical
Technologies**
Christian Sommer

**Laser and Plasma
Processing**
Wolfgang Waldhauser

**Sensors and
Functional Printing**
Jan Hesse

Smart Connected Lighting
Andreas Weiss

Roll-2-Roll UV-NIL Pilot Line

an optimized value chain for micro-optics

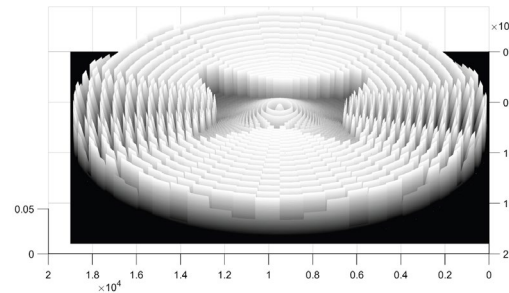
3

MATERIAL



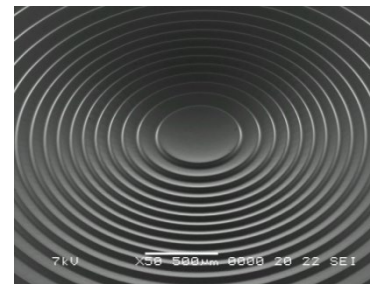
e.g. Poly-
Urethane-
Acrylates

SIMULATION & DESIGN



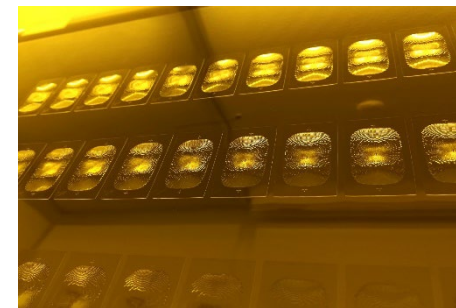
e.g. COMSOL,
Ray Tracing

MASTER



e.g. Maskless
Laser Lithography

STAMP / SHIM



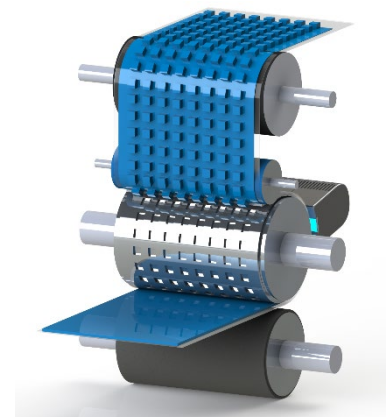
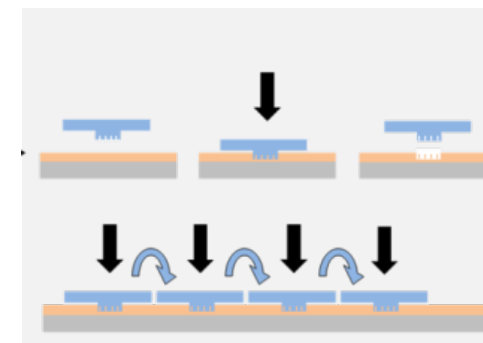
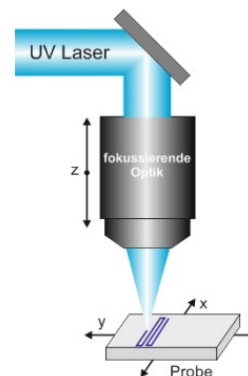
Step & Repeat UV-NIL

PRODUCTION



R2R-UV-NIL

MICRO-OPTICS IS...
Phabulous

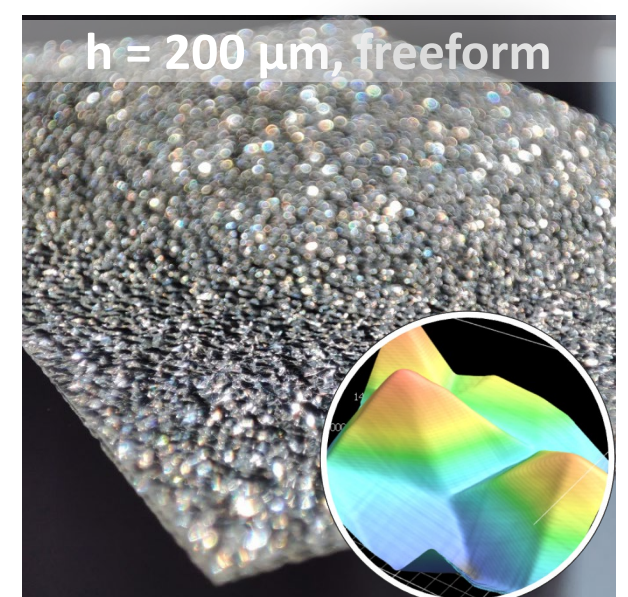
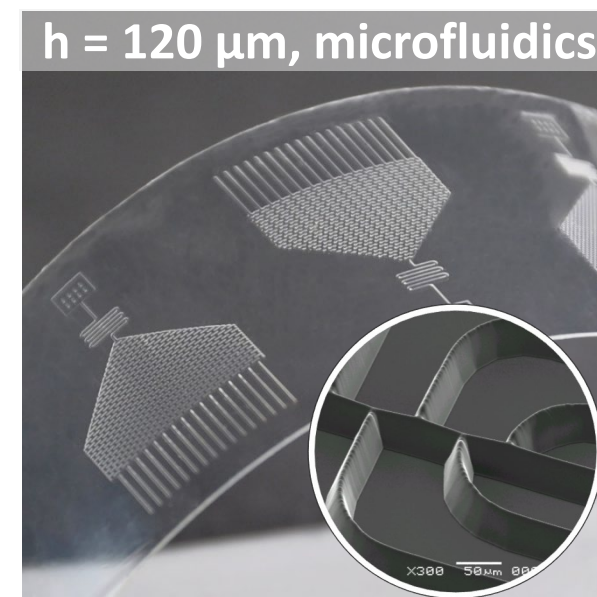
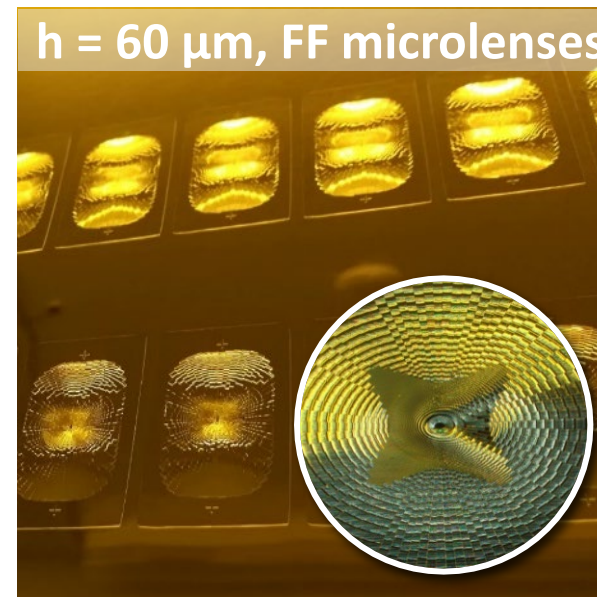
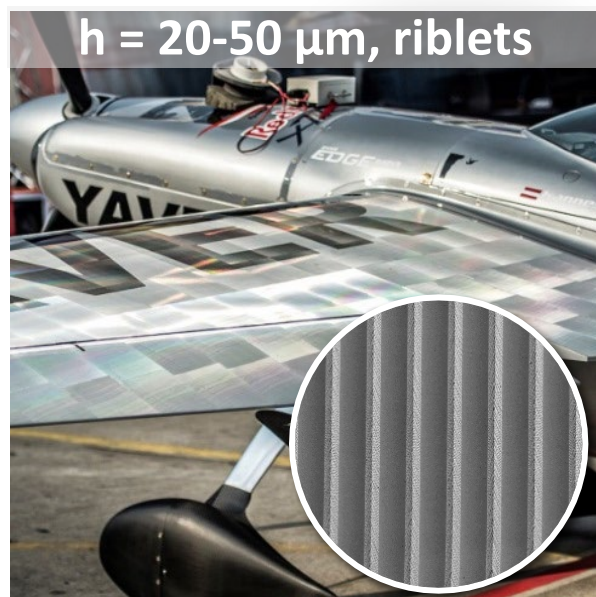
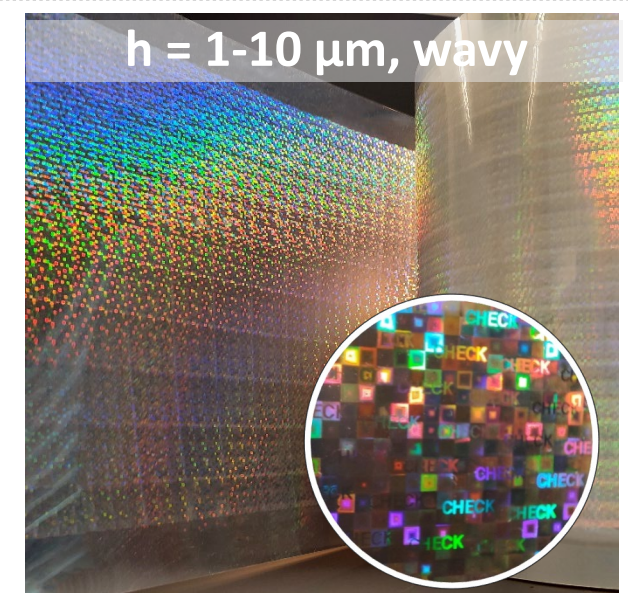
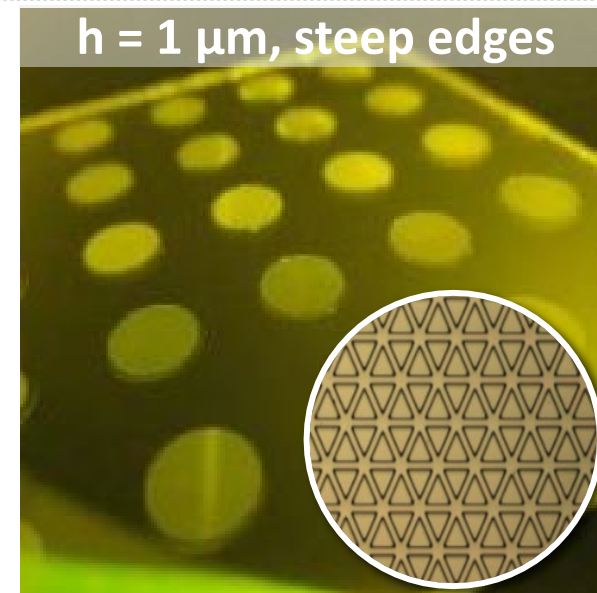
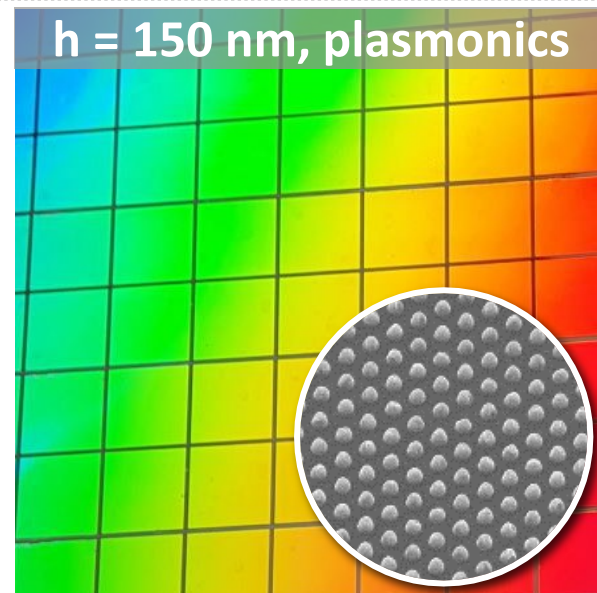
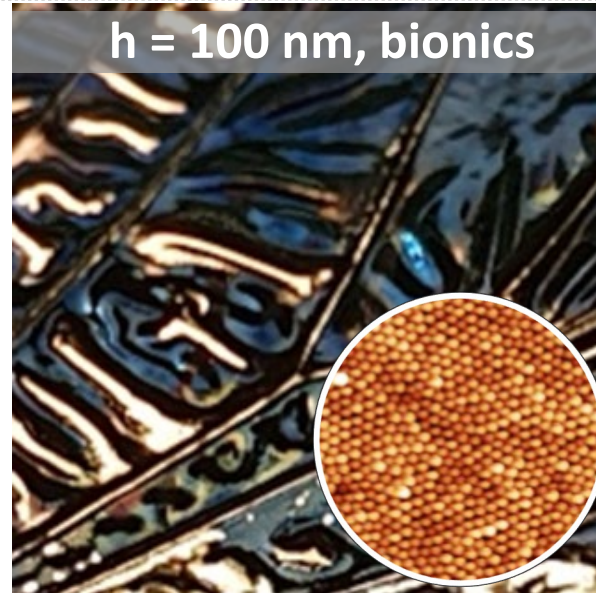


UPSCALING

Application examples of nano and micro imprinting

Structures range from 100nm to 200 μ m

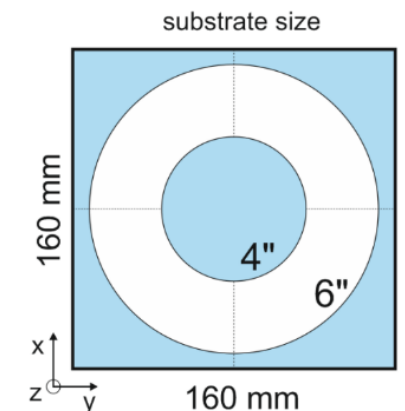
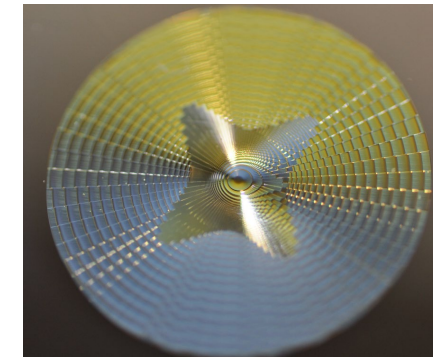
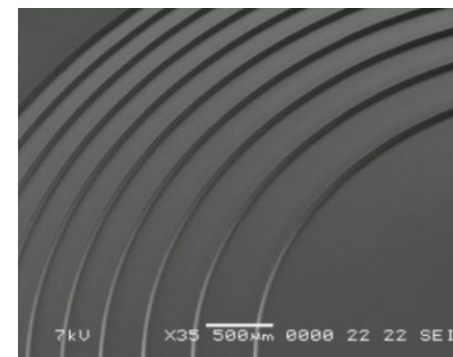
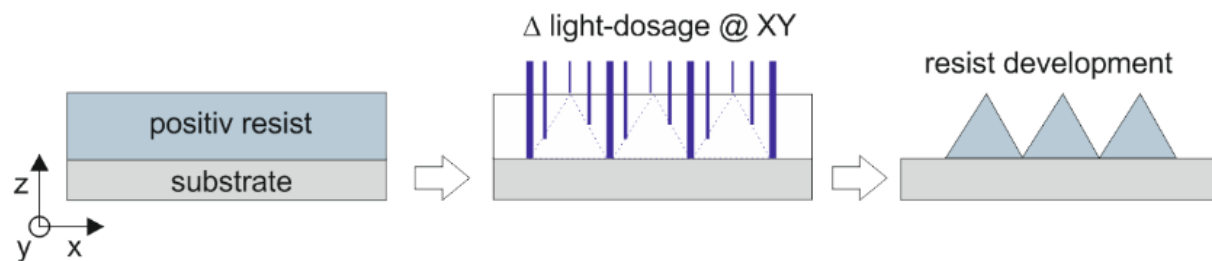
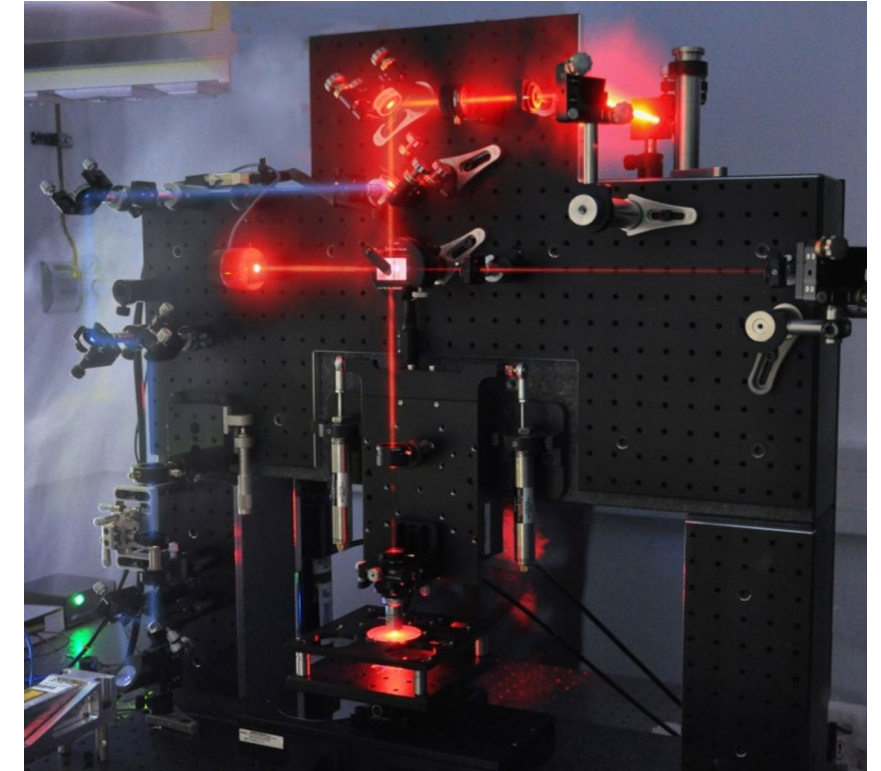
4



Mastering: Grey Scale Lithography

Main features (Status 2024)

- Structuring on planar and curved substrates
- Min. feature size(XY): 200 nm
- Max. structure height(Z): 60 μm
- Aspect ratio: 4:1
- Structure type: 1D, 2D, 2.5D and free-form
- Writing speed (CD = 1 μm) 1 cm^2/h
- Max. area 16 x 16 cm^2 (6" x 6")



Ongoing Developments in Laser Lithography

Integration of different laser lithography technologies, quality monitoring systems and processes in **one platform** for the development of **structures with high depth** (from **100 nm** to **sub-mm**), **2D & 3D shapes** on flat surface, combining **parallel & serial patterning** for increased speed and large area (up to 2000cm²)

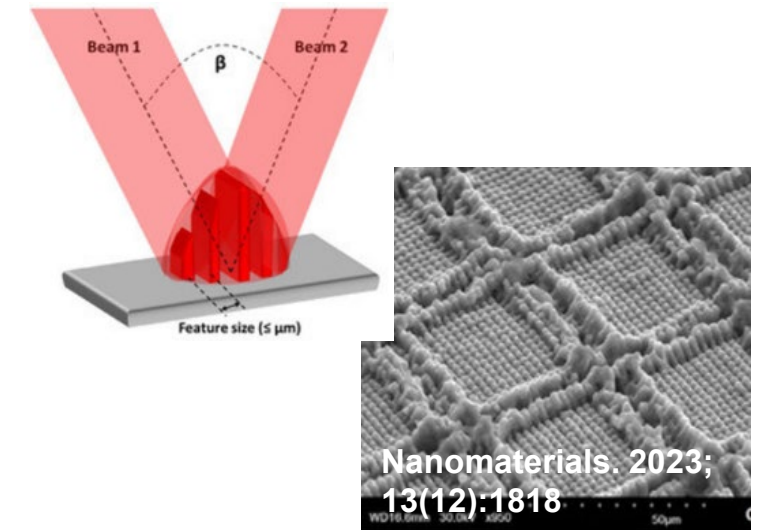
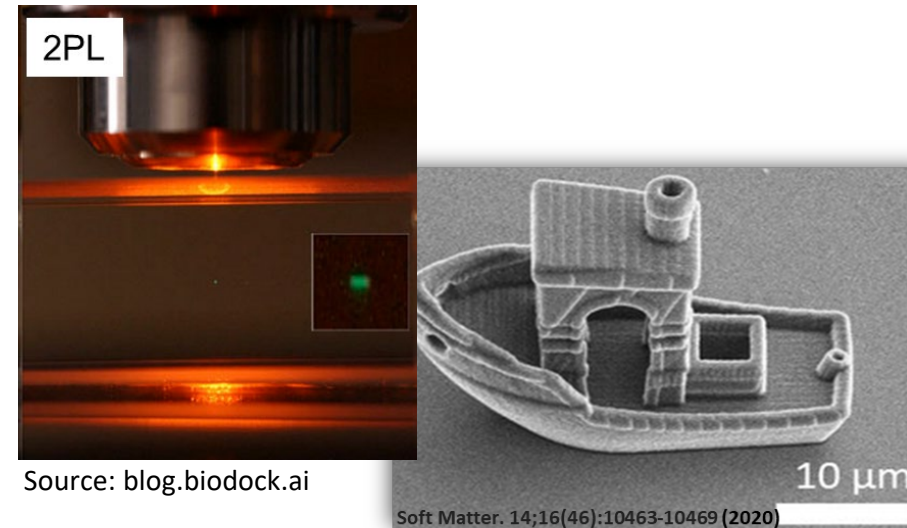
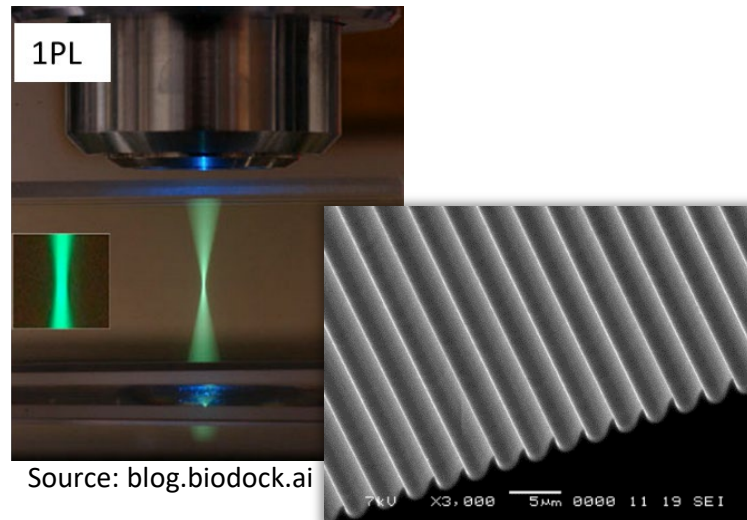
One-Photon Lithography (1PL)

+

Two-Photon Lithography (2PL)

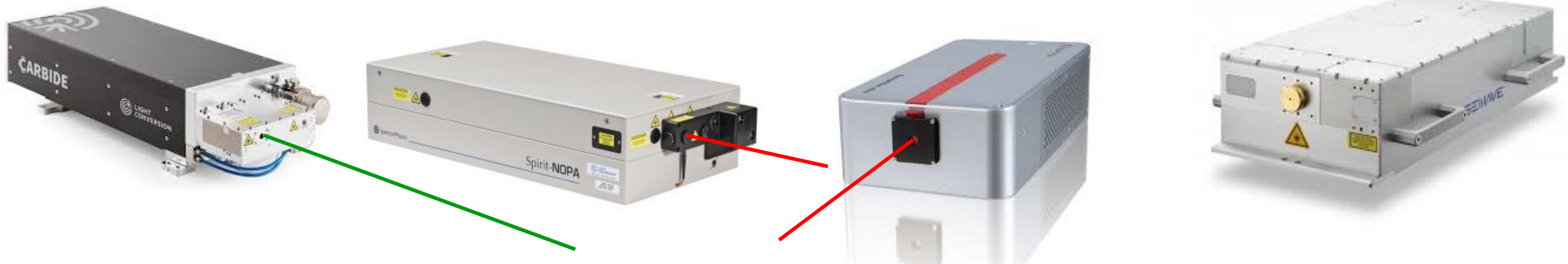
+

Laser Interference Lithography (LIL)

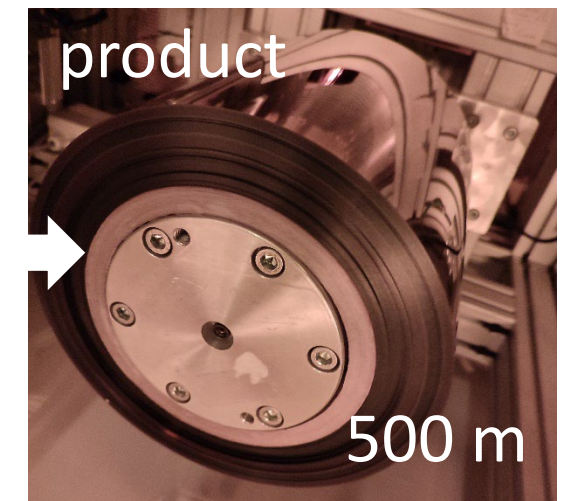
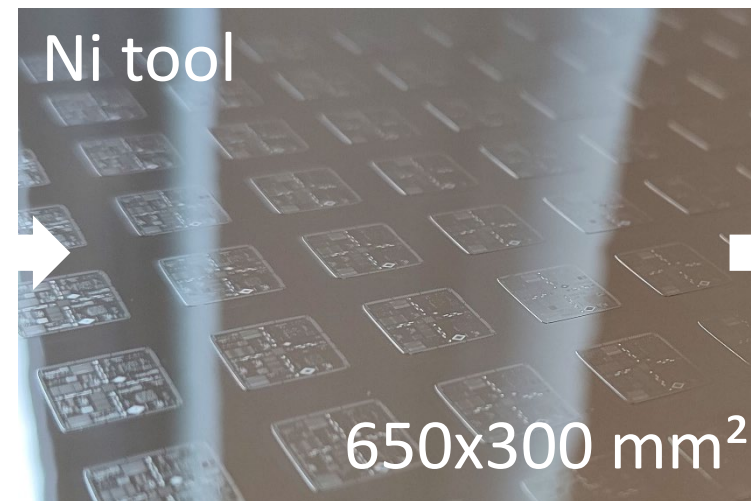
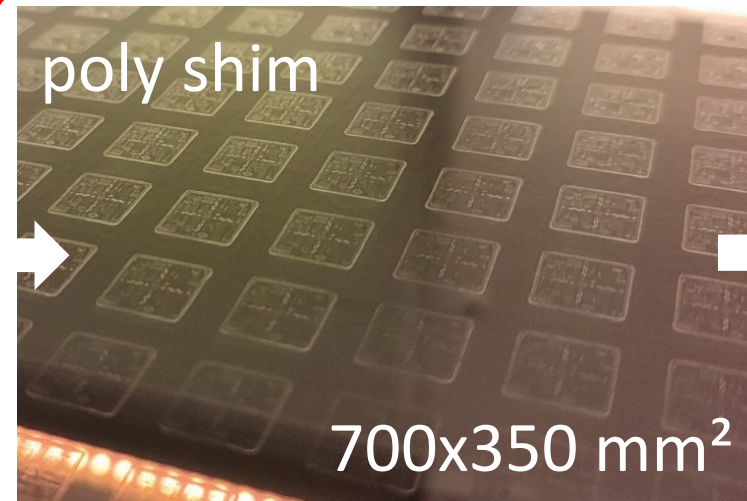
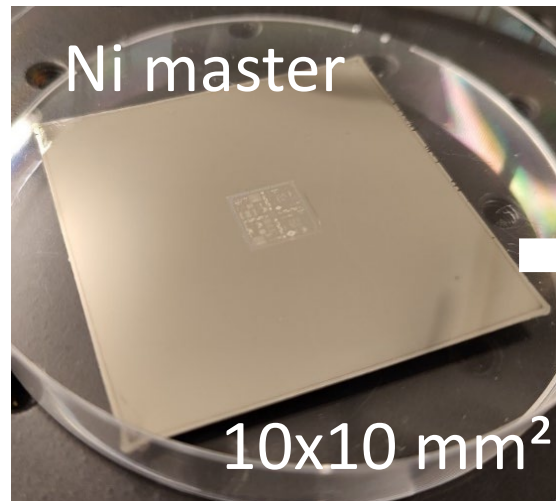


Laser Micromachining at JR MATERIALS

- Modern ultrashort pulse (USP) laser labs
 - Light Conversion Carbide fs-Laser
 - Spectra Physics Spirit fs-Lasers
 - Toptica fs-Laser
 - Edgewave ps-Laser
 - Trumpf ns-Laser
- High-precision xy-stages
- Galvoscaners (synchr.)
 - Working range: max. 210 mm × 210 mm
- Cleanroom Class 6, ISO 14644



Large-area tooling is still a bottleneck



Typical active area from origination (for freeform, nano, high AR, hierarchical...):
10 x 10 mm² – 30 x 30 mm²

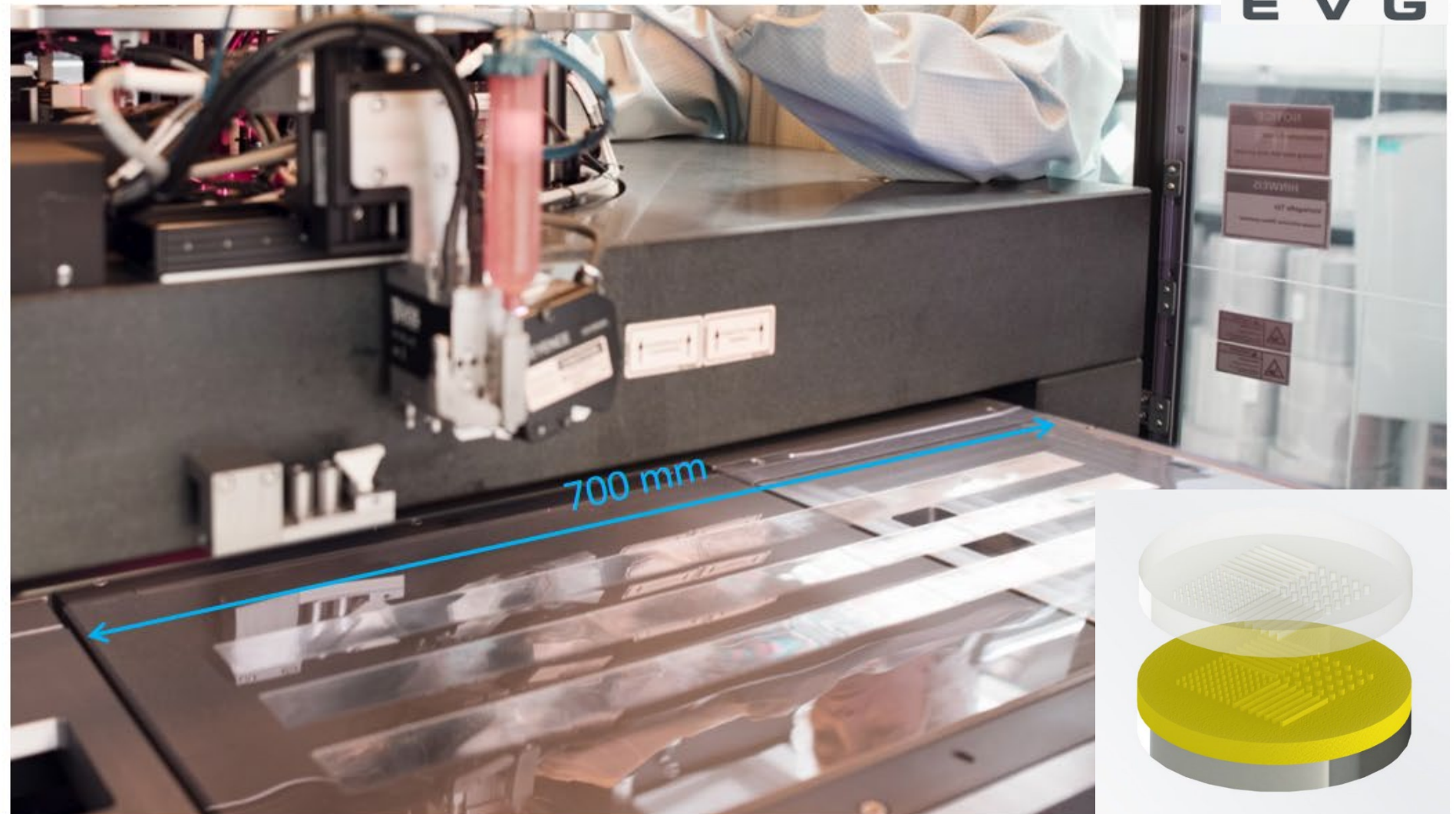
Typical master materials:
resin, Ni, Si, quartz, silicones,...

We need **powerful, flexible and highly accurate** upscaling and tooling processes.

Step & Repeat upscaling @JR

Max. substrate area: 700 x 380 mm²
(Tool size for R2R@JR: 630 x 270 mm²)

Stage positioning accuracy: ~3 µm
Overlay alignment accuracy: <1 µm

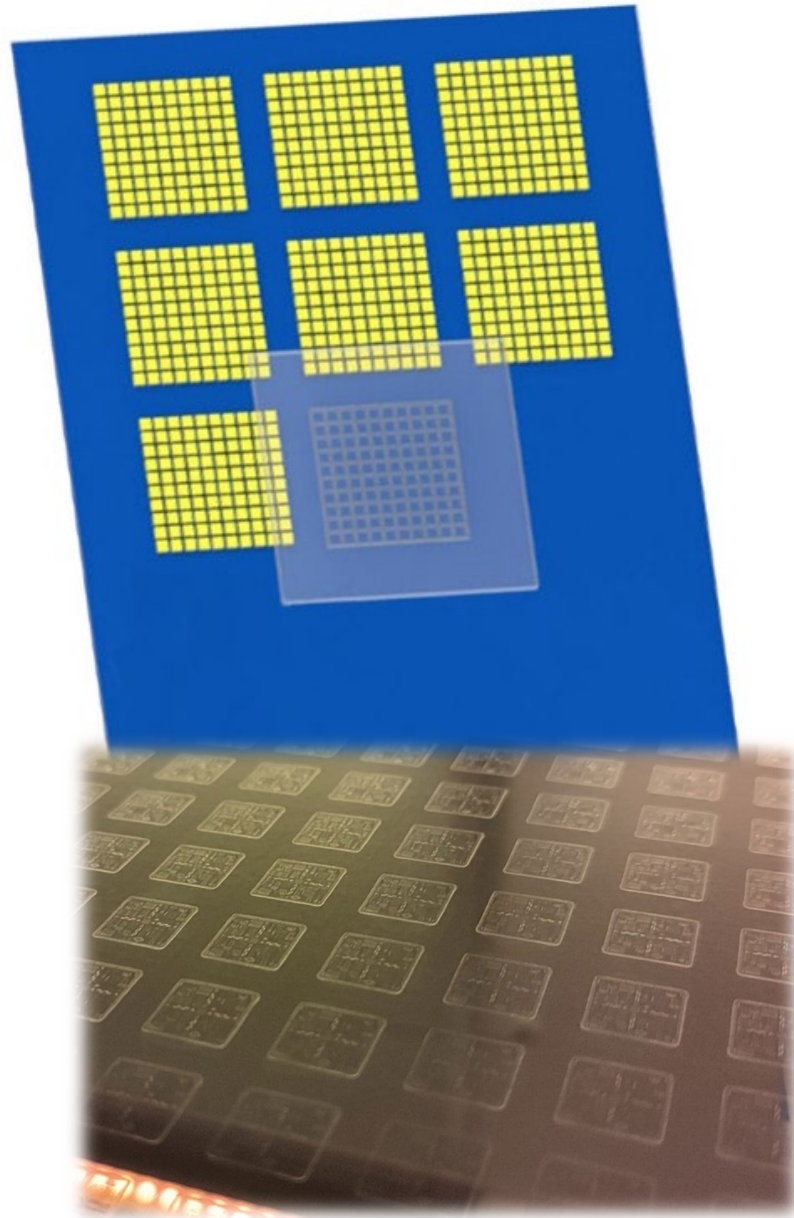


Customized EVG 770



Step & Repeat UV-NIL Upscaling From master to poly-shim

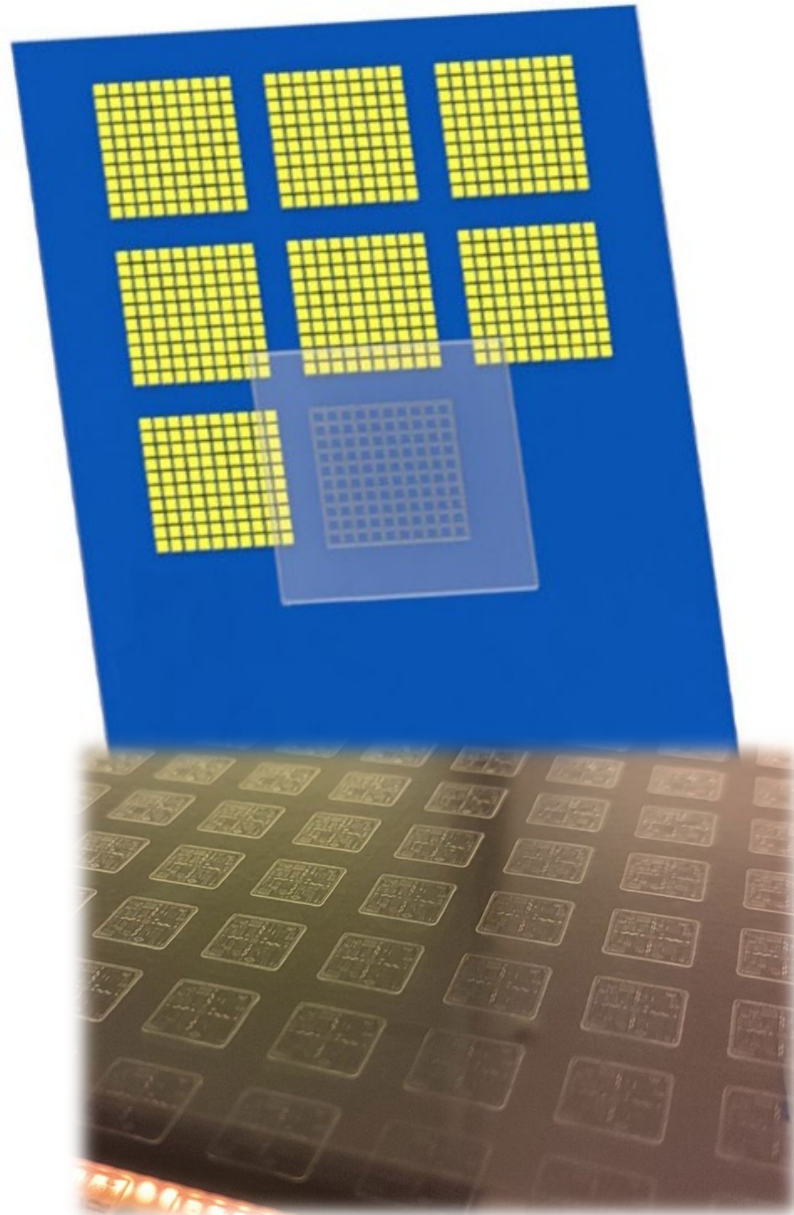
10



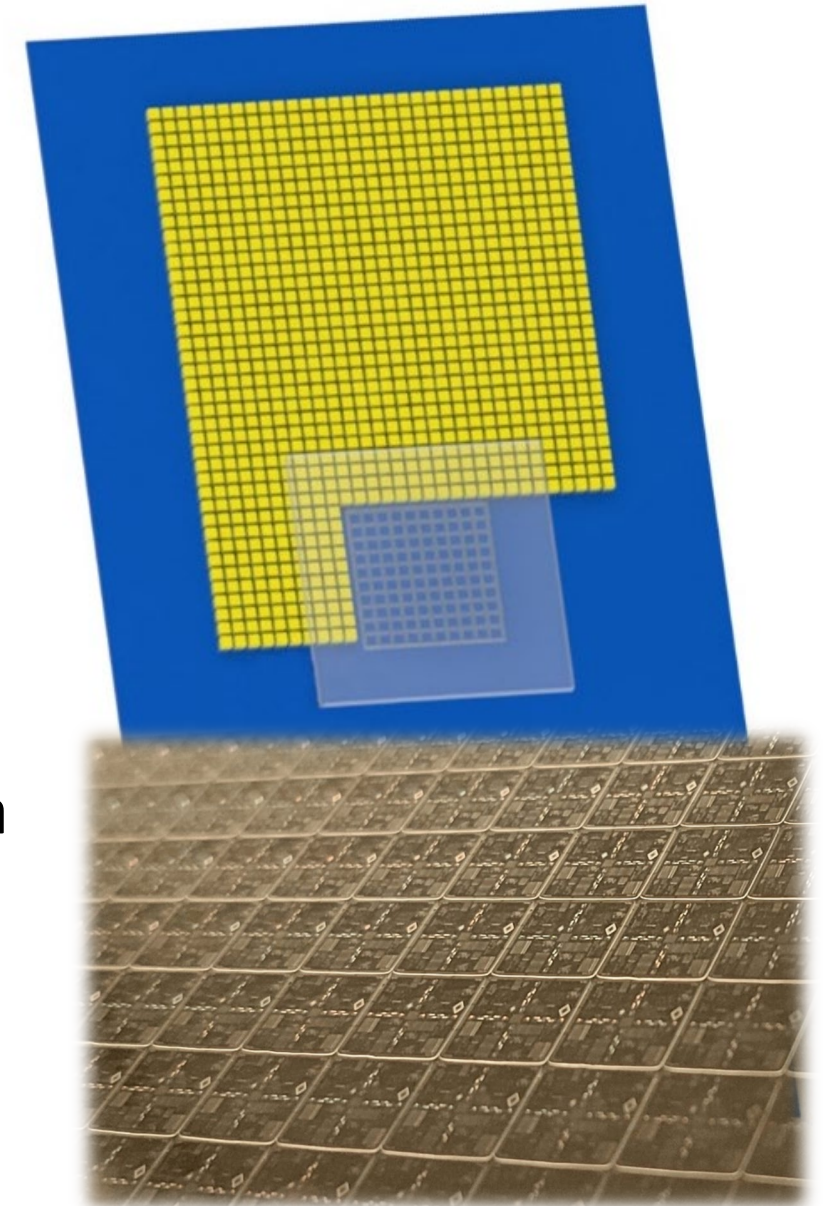
1) Multiple replication of a small master field on a larger area **with given distance** to each other

Step & Repeat UV-NIL Upscaling From master to poly-shim

11



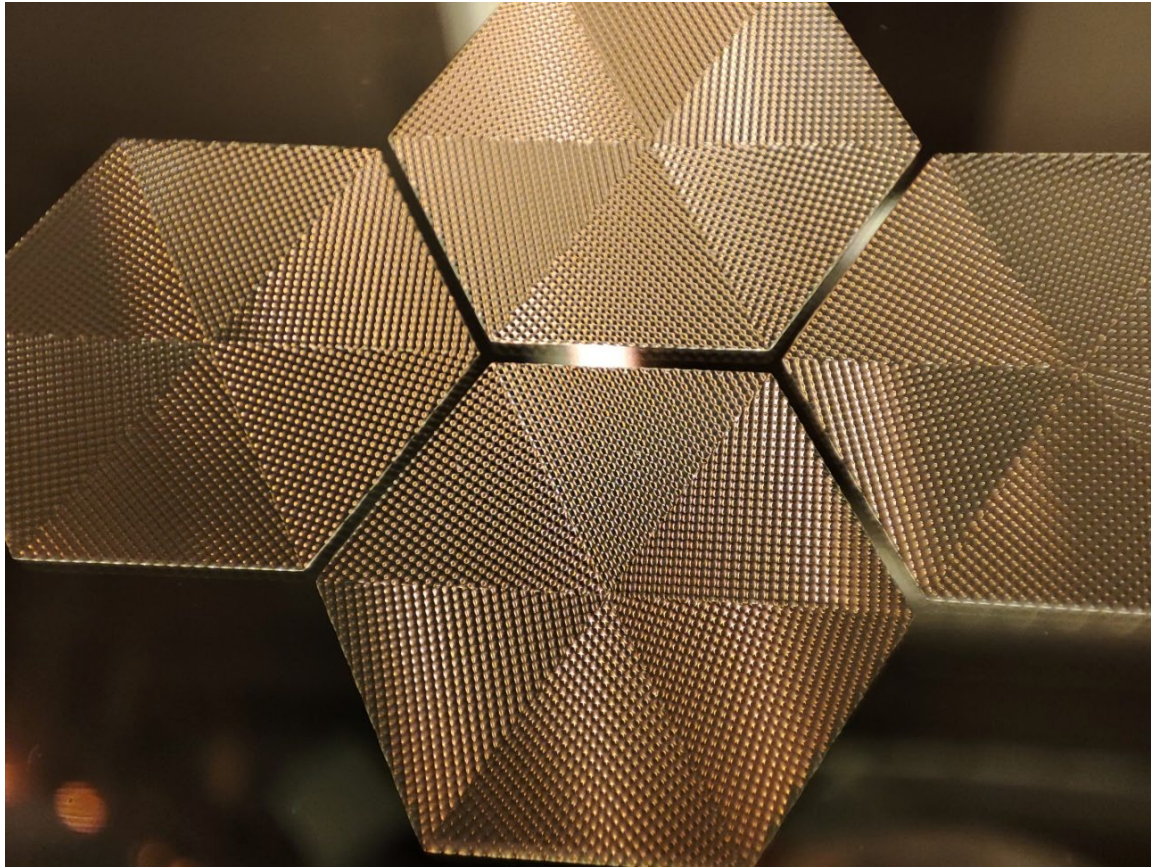
1) Multiple replication of a small master field on a larger area **with given distance** to each other



2) Multiple replication of a small master field **with minimum distance** to each other or „seamless“

12

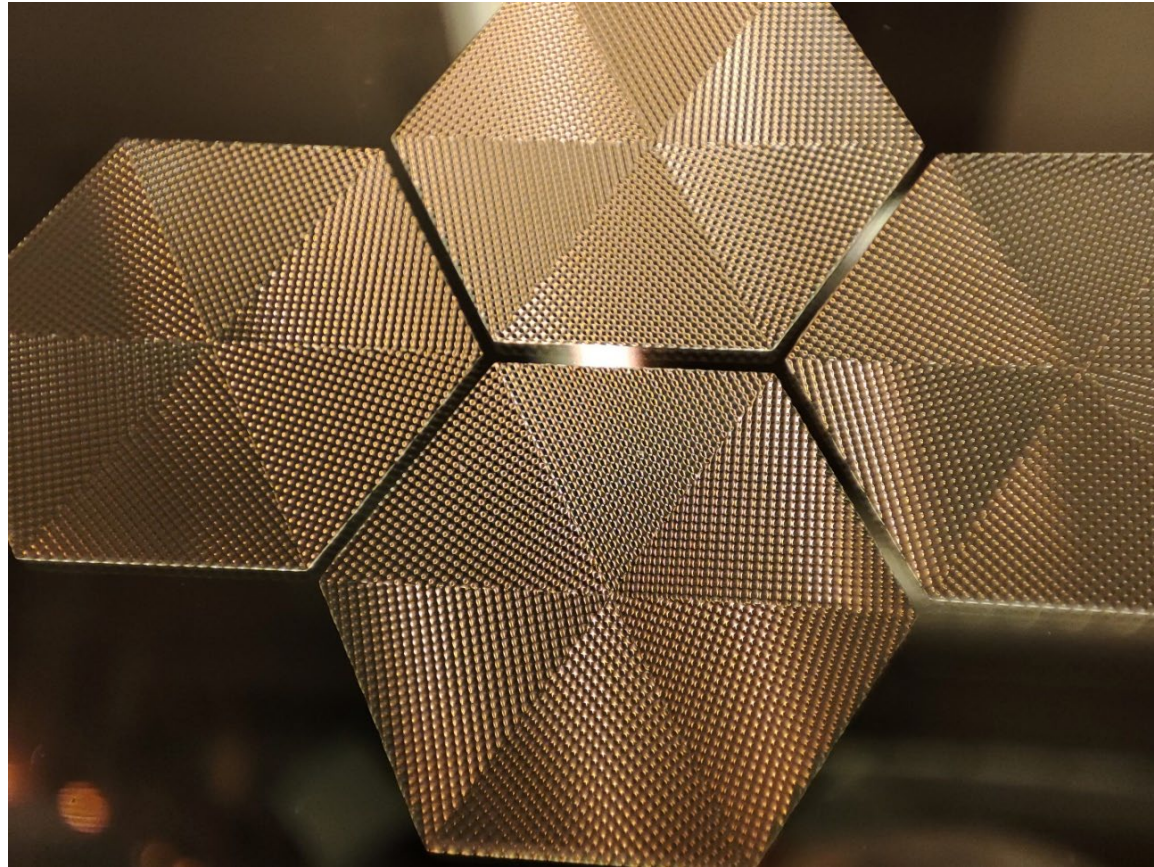
Seamless Step & Repeat Upscaling



Step&Repeat UV imprints on PET foil
distance = 1 mm

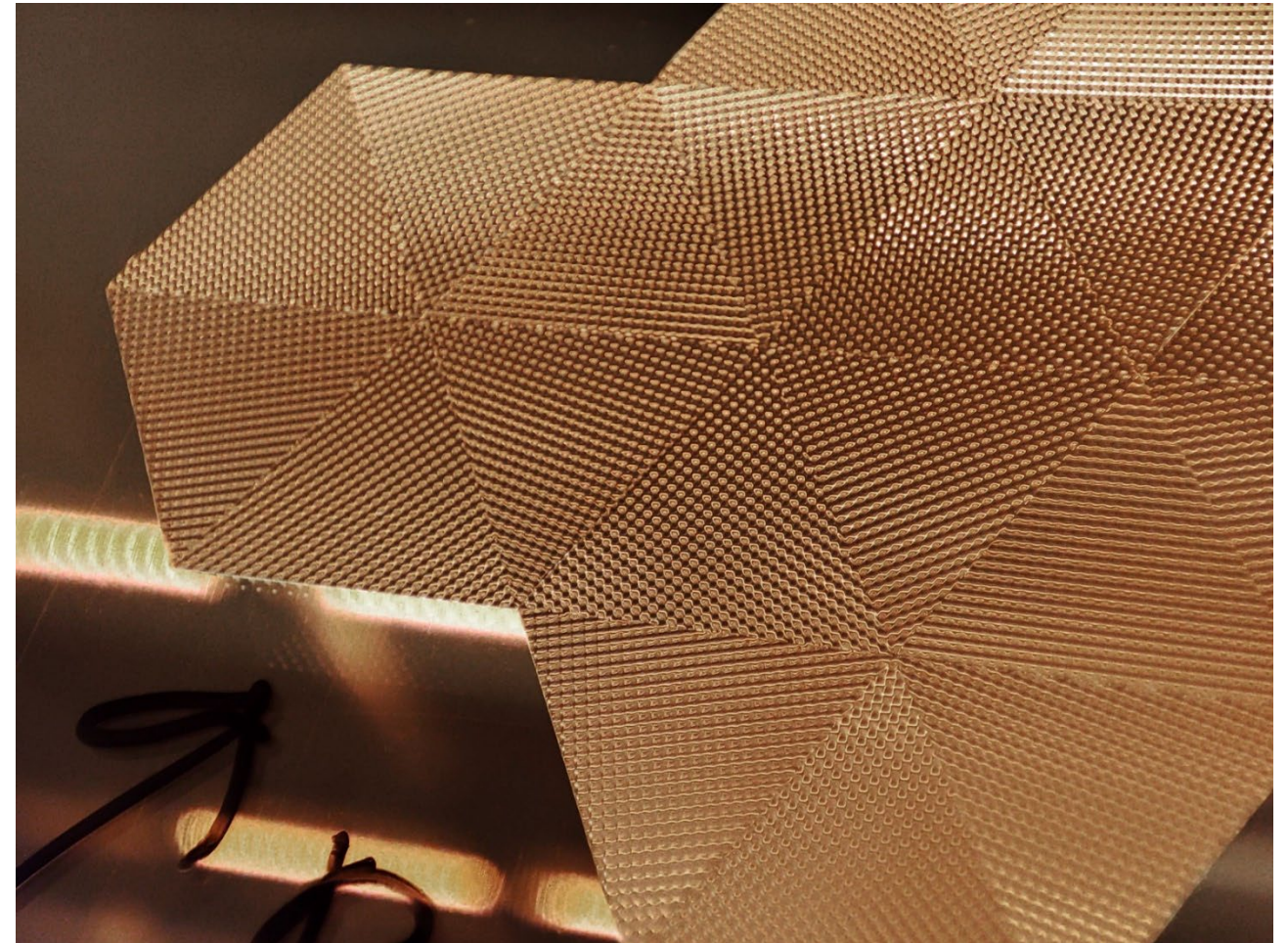
13

Seamless Step & Repeat Upscaling



Step&Repeat UV imprints on PET foil
distance = 1 mm

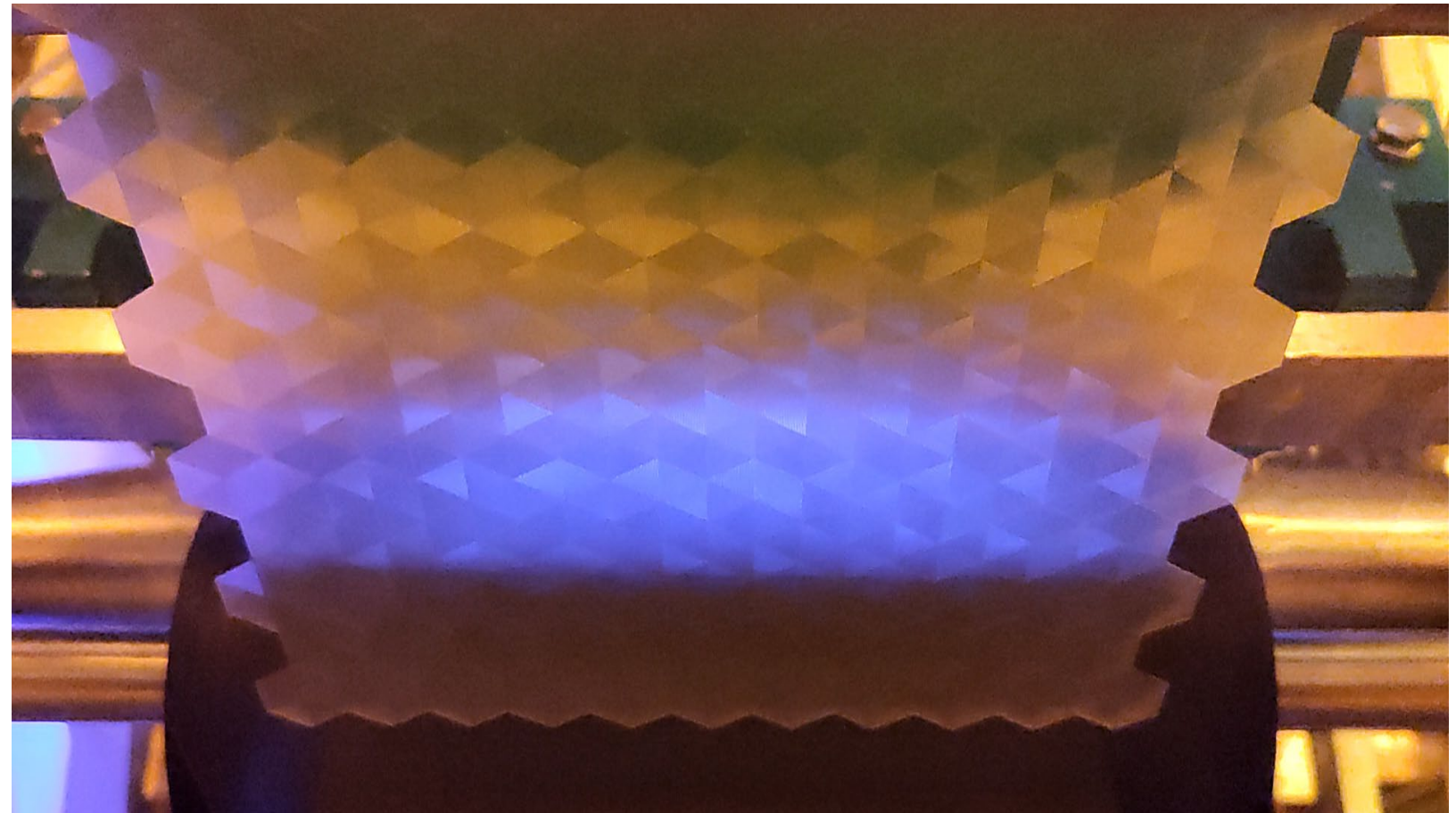
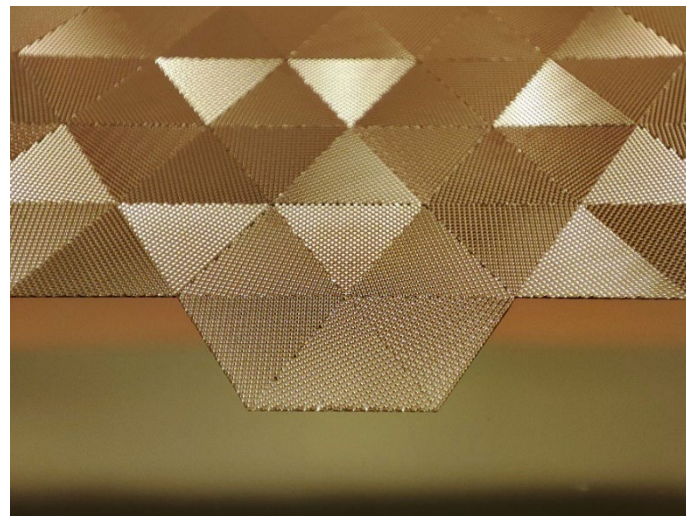
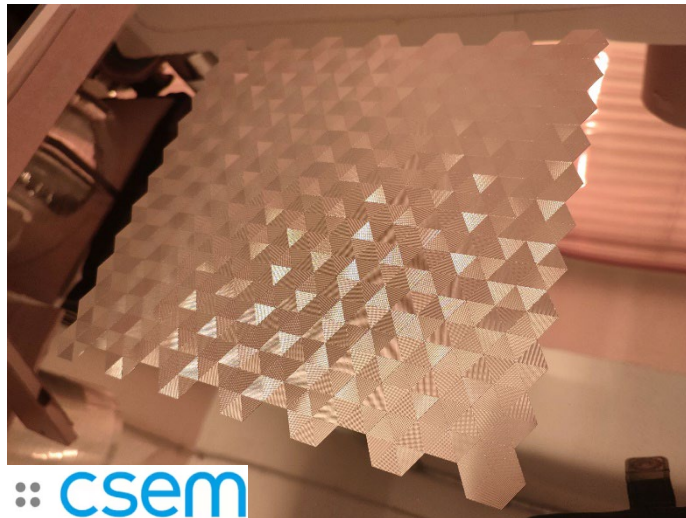
Distance and
rotation optimization



14

Roll-to-Roll (R2R) replication

Converting the poly-shim
to a durable Ni tool



Use Case 1: Decorative Films

Application:

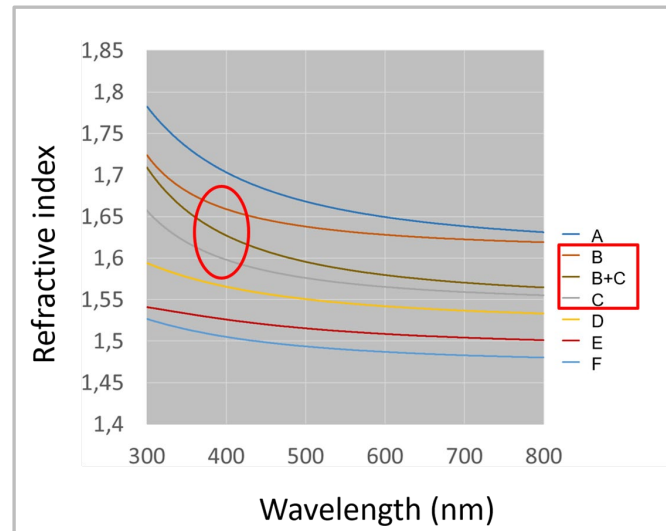
Freeform micro-facets to realize a sparkling effect for luxury goods

Upscaling target: Seamless Step & Repeat Upscaling for Roll-to-Roll production

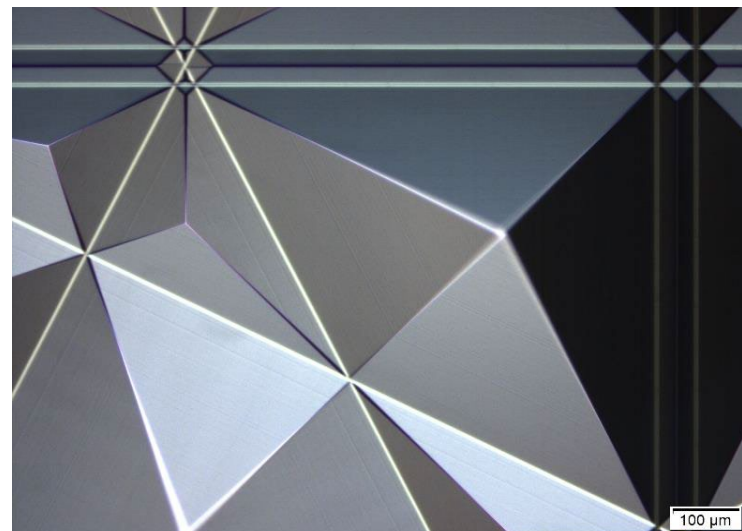
Seamless stitching of distributed facets with extremely high edge accuracy, low shrinking and low Abbe number



Resin with high dispersion



„Crystals“ with facet designs



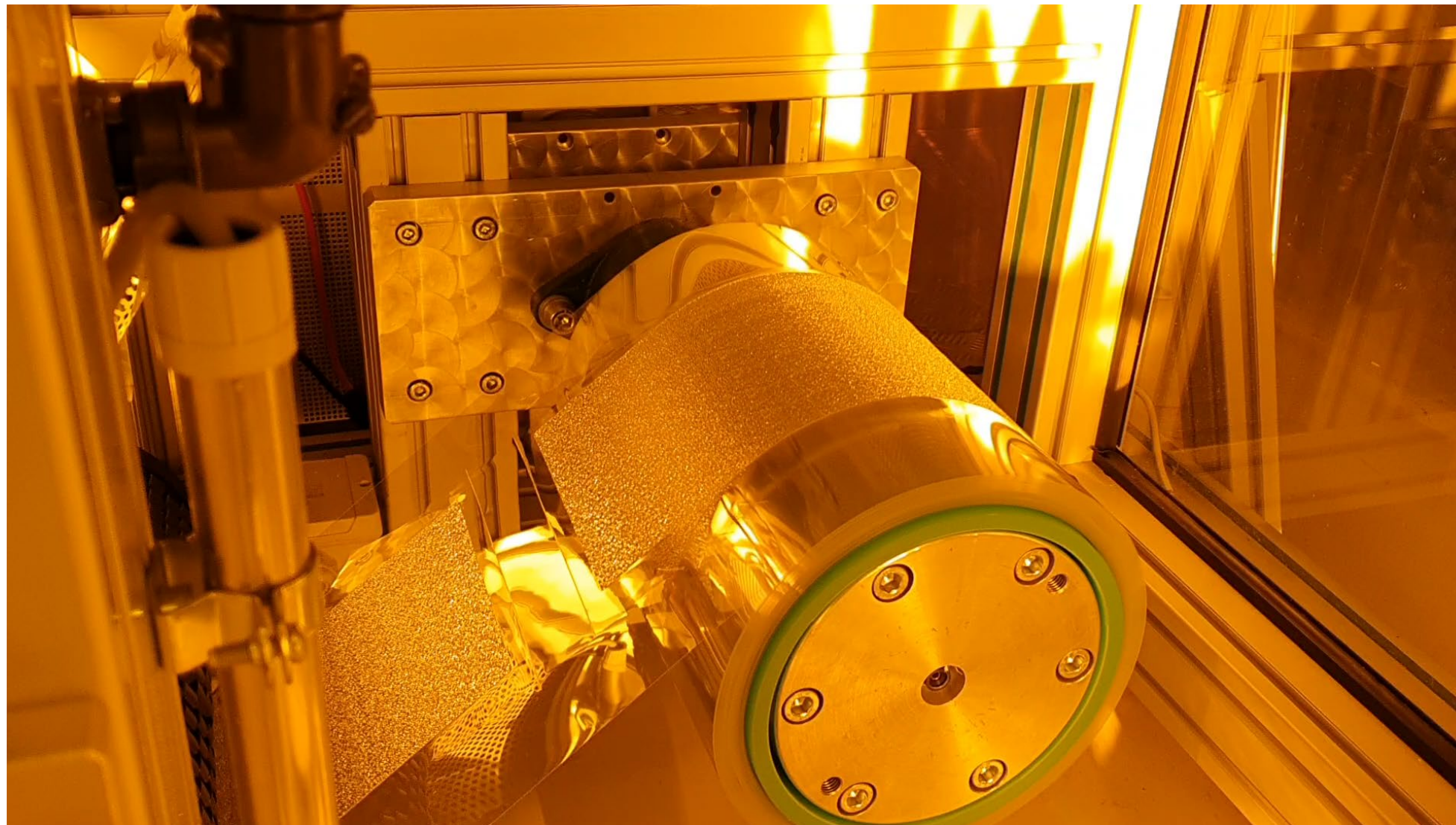
Double side imprinted „crystals“



16

Roll-to-roll (R2R) replication of facets with high accuracy of replication

R2R UV imprint into high index, high dispersion resin




video

$v = 1 \text{ m/min}$

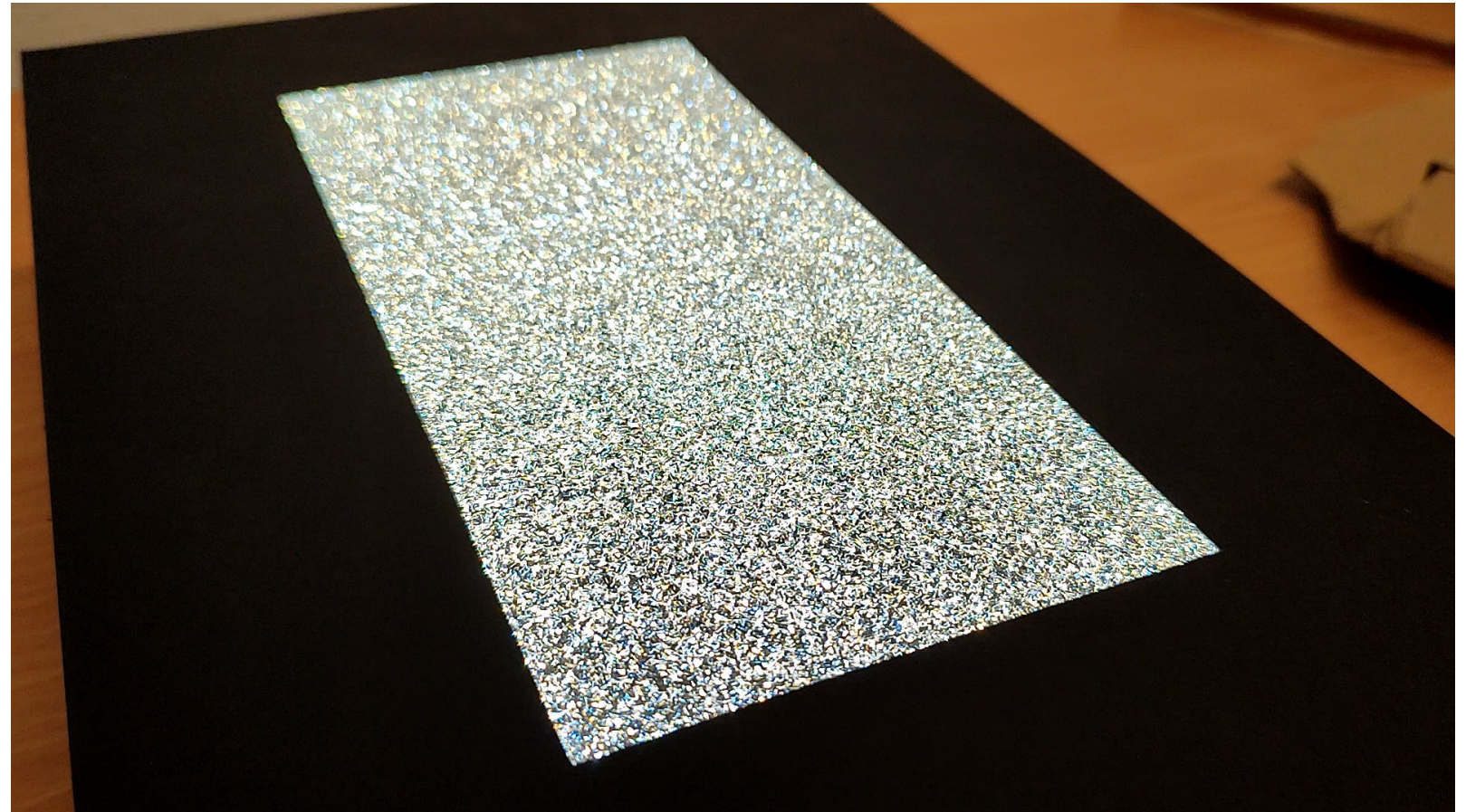
17

Roll-to-roll (R2R) replication: finished products



R2R UV imprint into **high dispersion resin**
+ R2R backside metallized  Fraunhofer
View: reflection

video



R2R UV imprint into **high dispersion resin**
View: transmission

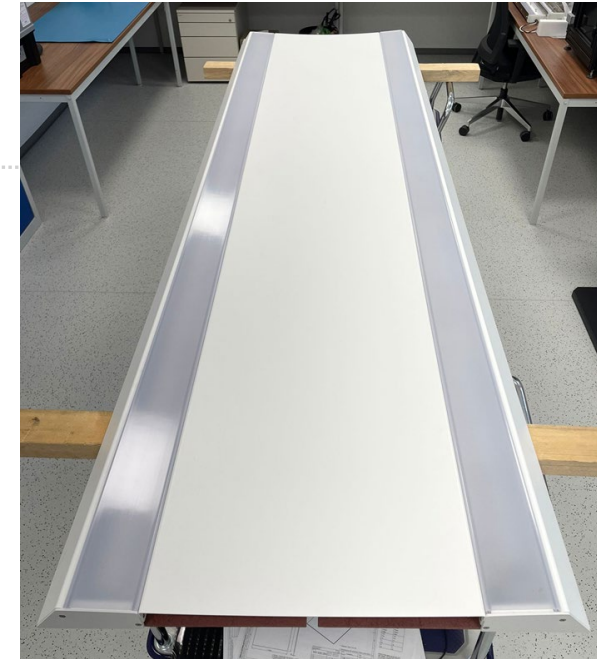
Use Case 2: Interior Lighting for Trains

Application:

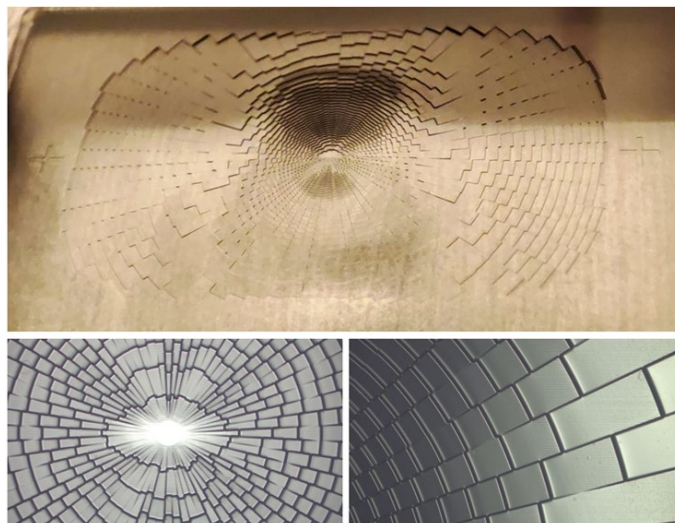
Freeform micro-lenses for a homogeneous large-area direct-lit luminaire as a linear lens array

Upscaling target: Grey Scale Lithography Mastering, Step & Repeat and Roll-to-Plate production

Freeform lenses with highest surface quality and shape fidelity



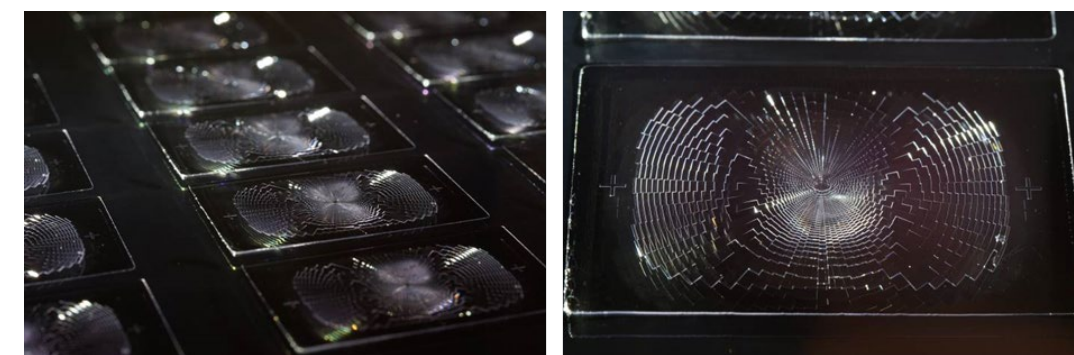
S&R working stamp



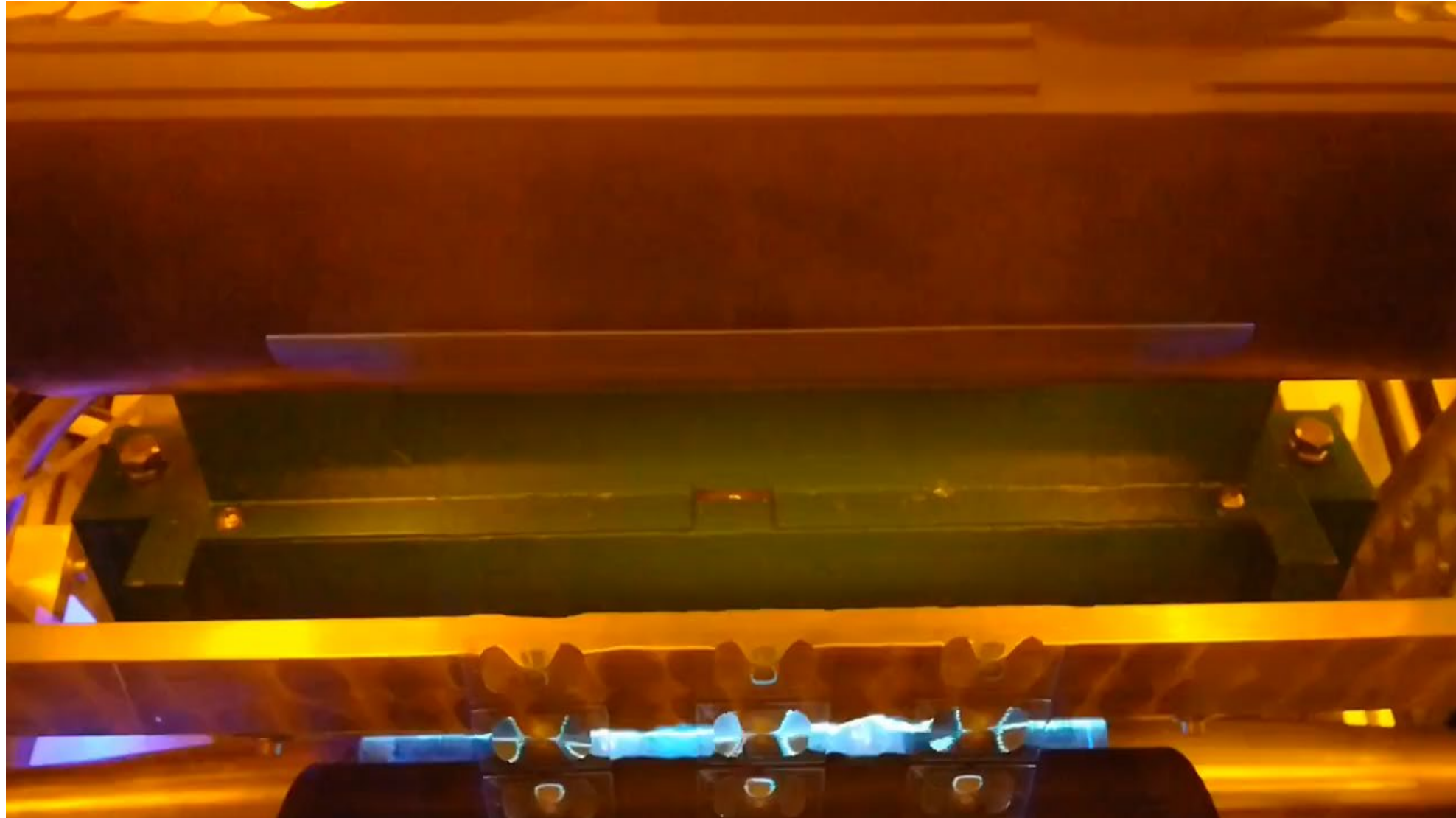
Polymer shim



Roll-to-Plate lens arrays



Roll-to-Roll replcation of FF-Microlenses



Special Thanks to
Ursula Palfinger, Roman Trattnig, Markus Postl, Stephan Ruttloff

Thank you for your attention!

JOANNEUM RESEARCH
Forschungsgesellschaft mbH

MATERIALS –
Institute for Sensors, Photonics and Manufacturing Technologies

Franz-Pichler-Straße 30
8160 Weiz, Austria

Tel. +43 316 876-3000
materials@joanneum.at

www.joanneum.at/materials

